

IN THE CLAIMS:

Please amend claims 1, 3-4, 7 and 9-10 as follows:

LISTING OF CURRENT CLAIMS

Claim 1. (Currently Amended) A method of forming a TFT-LCD device on a transparent insulating substrate wherein a transistor is defined on the transparent insulating substrate, the method comprises the following steps of:

forming a photosensitive layer on said transparent insulating substrate to cover said transistor and said transparent insulating substrate;

performing a defocused exposing procedure by applying a mask with ~~plural~~ a plurality of independent spot patterns and a contact hole pattern to define patterns on said photosensitive layer, wherein a distance between two adjacent said independent spot patterns is smaller than a resolution of an exposure system while a distance between adjacent said independent spot pattern and said contact hole pattern is larger than said resolution of said exposure system, wherein a first area of said photosensitive layer corresponding to said independent spot patterns is exposed incompletely while a second area thereof corresponding to said contact hole pattern is exposed completely;

developing said photosensitive layer to partially remove ~~partial~~ said photosensitive layer of said first area ~~for forming wave-like~~ to form wave shaped surfaces thereon and to partially remove ~~partial~~ said photosensitive layer of said second area ~~for forming~~ to form a contact hole thereon; and

forming a pixel electrode on said photosensitive layer to fill said contact hole to electrically connect to said transistor, wherein said pixel electrode rises and falls with the surface of said photosensitive layer to server as a rough diffuser member.

Claim 2. (Original) The method of Claim 1, wherein a size of said contact hole pattern is larger than a size of said independent spot pattern.

Claim 3. (Currently Amended) The method of Claim 1, wherein sizes and shapes of said independent spot patterns ~~can be~~ are adjusted to control roughness degrees of pixel electrode.

Claim 4. (Currently Amended) The method of Claim 1, wherein sizes and shapes of said independent spot patterns ~~can be~~ are adjusted to control roughness degrees of said photosensitive layer.

Claim 5. (Original) The method of Claim 1, wherein said independent spot patterns are defined by forming hollow areas on said mask.

Claim 6. (Original) The method of Claim 1, wherein said independent spot patterns are defined by forming the covering area on said mask with chromium films.

Claim 7. (Currently Amended) A method of forming a TFT-LCD device on a transparent insulating substrate wherein said transparent insulating substrate has a gate structure and an insulating layer covered thereon, and a drain structure and a source structure formed on said insulating layer, the method comprises the following steps of:

forming a photosensitive passivation layer on said transparent insulating substrate to cover said source structure, said drain structure and said insulating layer;

performing a patterning procedure by applying a mask with ~~plural~~ a plurality of independent spot patterns and a contact hole pattern to define patterns on said photosensitive passivation layer, wherein a first area of said photosensitive passivation layer corresponding to said independent spot patterns is exposed incompletely while a second area thereof corresponding to said contact hole pattern is exposed completely;

developing said photosensitive passivation layer to partially remove ~~partial~~ said photosensitive layer of said first area ~~for forming wave-like~~ to form wave shaped surfaces thereon and to partially remove ~~partial~~ said photosensitive material of said second area ~~for forming~~ to form a contact hole thereon; and

forming a pixel electrode on said photosensitive passivation layer to fill said contact hole to electrically connect with said drain structure, wherein said pixel electrode rises and falls with the surface of said photosensitive passivation layer to server as a rough diffuser member.

Claim 8. (Previously Amended) The method of Claim 7, wherein a size of said contact hole pattern is larger than a size of said independent spot pattern.

Claim 9. (Currently Amended) The method of Claim 7, wherein sizes and shapes of said independent spot patterns ~~can be~~ are adjusted to control roughness degrees of said pixel electrode.

Claim 10. (Amended) The method of Claim 7, wherein sizes and shapes of said independent spot patterns ~~can be~~ are adjusted to control roughness degrees of said photosensitive passivation layer.

Claim 11. (Previously Amended) The method of Claim 7, wherein said independent spot patterns are defined by forming hollow areas on said mask.

Claim 12. (Previously Amended) The method of Claim 7, wherein said independent sport patterns are defined by forming the covering area on said mask with chromium films.

Claim 13. (Previously Amended) The method of Claim 7, wherein a first distance between two adjacent said independent spot patterns is smaller than a resolution of an exposure system while a second distance between adjacent said independent spot pattern and said contact hole pattern is larger than said resolution of said exposure system.

Claims 14-20. (Previously Withdrawn)